

Sheet 1 of 1Substitute Form PTO-1449  
(Modified)U.S. Department of Commerce  
Patent and Trademark OfficeAttorney's Docket No.  
05542-443001Application No.  
09/903,052**Information Disclosure Statement  
by Applicant**

(Use several sheets if necessary)

(37 CFR §1.98(b))

Applicant  
Arkadiy Yampolskiy, et al.Filing Date  
July 10, 2001Group Art Unit  
3723**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
LW	AA	2001/015811	08/23/2001	Ravid, et al.			
	AB	2001/026364	10/04/2001	Ravid, et al.			
	AC	2002/005957	01/17/2002	Moshe, et al.			
	AD	5,486,129	01/23/1996	Sandhu, et al.			
	AE	5,658,183	08/19/1997	Sandhu, et al.			
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	AG	6,159,073	12/12/2000	Wiswesser, et al.			
	AH	6,261,152 B1	07/17/2001	Aiyer			
	AI	6,829,054 B2	12/00/2004	Stanke, et al.			
	AJ						
	AK						

**Foreign Patent Documents or Published Foreign Patent Applications**

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
LW	AL	JP 9148284	06/06/1997	JP				
	AM	WO 99/25520	05/27/1999	WIPO				
	AN							
	AO							
	AP							

**Other Documents (include Author, Title, Date, and Place of Publication)**

Examiner Initial	Desig. ID	Document
LW	AQ	Pan, J. Tony, et al., "Copper CMP and Process Control," Final Paper submitted to CMP-MIC Conference, February 11-12, 1999, Santa Clara, CA and Cambridge, MA, 7 pp.
	AR	Ravid, Avi, et al., "Copper CMP Planarity Control Using ITM," IEEE/SEMI Advanced Semiconductor Manufacturing Conference, 2000, pp. 437-443.
	AS	
	AT	

Examiner Signature

Date Considered

4/13/06

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute Disclosure Form (PTO-1449)